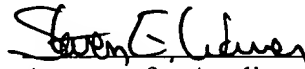


for these changes can be found in the original application as filed. Therefore, no new matter has been added.

Applicant submits that claims 16-19 and 22-24 patentably define features of the projection exposure apparatus of the present invention. Therefore, Applicant submits that the instant application is in condition for allowance. Favorable consideration and an early Notice of Allowance are requested.

Applicant's undersigned attorney may be reached in our Washington, D.C. office by telephone at (202) 530-1010. All correspondence should be directed to our address listed below.

Respectfully submitted,



Attorney for Applicant
Steven E. Warner
Registration No. 33,326

FITZPATRICK, CELLA, HARPER & SCINTO
30 Rockefeller Plaza
New York, New York 10112-3801
Facsimile: (212) 218-2200
SEW/eab

APPENDIX A

IN THE CLAIMS

16. (Amended) A projection exposure apparatus, comprising:

an illumination optical system for illuminating a reticle with light from a light source, wherein said illumination optical system includes an optical integrator for producing a secondary light [sources] source with [illumination light supplied] the light from the light source, and masking means for restricting an illumination range [to be defined on a surface which is to be illuminated with the illumination light] upon the reticle, which is to be illuminated with illumination light from the secondary light source;

a projection optical system for projecting a pattern of the reticle, as illuminated, onto a substrate;

measuring means for measuring telecentricity of said projection optical system with respect to different image heights; and

[adjusting] changing means for [adjusting] changing an incidence angle[, upon the reticle,] of the illumination light corresponding to each of the different image heights, to [correct] adjust the telecentricity with respect to [a respective] the image height, wherein said adjusting means moves an optical element disposed in a portion of said illumination optical system between said optical integrator and said masking means, along an optical axis direction[, to thereby change an angular distribution of illumination light entering said projection optical system].

18. (Amended) A projection exposure apparatus, comprising:

an illumination optical system for illuminating a reticle with illumination light
[from a light source];

a projection optical system for projecting a pattern of the reticle, as
illuminated, onto a substrate;

measuring means for measuring telecentricity of said projection optical system
with respect to different image heights, [wherein] said measuring means also [measures]
measuring telecentricity [of said projection optical system] with respect to an optical axis;

first [adjusting] changing means for [adjusting] changing an incidence angle[,
upon the reticle,] of the illumination light corresponding to each of the different image
heights, to [correct] adjust the telecentricity with respect to [a respective] the image height;
and

second [adjusting] changing means for [adjusting] changing an incidence angle
of the illumination light [upon the reticle] to [correct] adjust the telecentricity with respect
to the optical axis.